CLAIMS

1. A polishing composition for polishing an object including a metal portion or an interlayer insulation film, the polishing composition comprising silica on which an organic acid is immobilized to the surface through a silane coupling agent, an oxidizing agent, and an ammonium salt selected from the group consisting of ammonium chloride, ammonium perchlorate, ammonium sulfate, ammonium nitrate, and ammonium acetate, wherein the silica has an average degree of association of 1.2 or more and 4.0 or less.

2. The polishing composition according to claim 1, further comprising an anticorrosive agent.

3. The polishing composition according to claim 1 or 2, wherein the polishing composition has a pH of 6 or less.

4. A method for polishing, comprising polishing an object including a metal portion or an interlayer insulation film with the polishing composition according to any one of claims 1 to 3.

5. A method for producing a polished substrate, comprising the step of polishing an object including a metal portion or an interlayer insulation film with the polishing composition according to any one of claims 1 to 3.